



SHEET 1 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION			ATTY. DOCKET NO. 055071-0310	SERIAL NO. 10/705,234			
			APPLICANT Armin LIEBCHEN				
(PTO-1449)			FILING DATE November 12, 2003	GROUP 2851			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ₂ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document			
<p><i>PK</i></p> <p><i>PK</i></p> <p><i>PK</i></p>		5,969,441	10/19/1999	Loopstra et al.			
	US	6,046,792	04/04/2000	Van Der Werf et al.			
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code-Number +-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes	Translation No
<p><i>PK</i></p>		WO 98/40791	09/17/1998	Konin Klijke Philips Electronics N.V.			
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
<i>Pete B. Kue</i>			EXAMINER	DATE CONSIDERED 9/13/05			

***EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.**

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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<i>PL</i>	US	5,880,588	10-21-1997	Gortych et al.		
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<i>PL</i>		JP 2000-232057A				X
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
<i>PL</i>		BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994) pp 6756-6764				
		M. DUSA et al., "Study of mask aerial images to predict CD proximity and line end shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159				
		B.P. MATHUR et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures," IEEE Transactions of Electron Devices, Vol. 35, No. 3 (March 1988), pp. 294-297				
		CHRISTOPHER J. PROGLER et al., "Merit functions for lithographic lens design," J. Vac. Sci. Technol. B 14(6), (Nov/Dec 1996), pp. 3714-3718				
<i>PL</i>		NISHRIN KACHWALA et al., "Imaging contrast improvement for 160 nm line features using sub resolution assist features with binary, 6% ternary attenuated phase shift mask with process turned resist," SPIE Vol. 3679 (1999), pp. 55-67				
<i>Pete D. K.</i>			DATE CONSIDERED <i>9/13/05</i>			

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